

### REMARKS

Claims 1-36 were presented for examination and are pending. Claims 26-35 are withdrawn. Claims 1-25 and 36 are rejected. Reconsideration is respectfully requested.

#### The Restriction Requirement

The applicant affirms the provisional election to prosecute the invention of Group I, claims 1-25 and 36. The traversal is withdrawn.

#### The 35 U.S.C. § 103 Rejections

Claims 1-25 and 36 are rejected as being unpatentable over Thilderkvist et al. in view of Montcalm et al. The rejection is respectfully traversed.

In Thilderkvist et al., a contaminated surface of a substrate processing chamber is coated with a layer of a material such that the contaminants are collected by the layer of material. A portion of the layer together with a portion of the contaminants is then removed. In the reference, the "surface" refers to "parts in a processing chamber such as a susceptor, wafer lift pins, or any other surfaces that will be in either direct or close contact with the wafer during processing". See column 3, lines 40-47. The reference does not disclose a step of removing a defect that is causing an amplitude defect from a multilayer coating, as recited by the applicants in claim 1. Emphasis added. The reference also fails to teach the step of etching away the damaged region.


Therefore the rejection of claim 1 should be withdrawn. The rejection of claims 2-25 and 36 should be withdrawn because they depend from claim 1. Therefore the rejection should be withdrawn.

Conclusions

It is submitted that this application is in condition for allowance based on claims 1-25 and 36 in view of the amendments thereto and the foregoing comments.

If any impediments remain to prompt allowance of the case, please contact the undersigned at 925-456-2279.

Respectfully submitted,

  
John P. Wooldridge  
Attorney for Applicant  
Registration No. 38,725

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